



The RIBE–450 is designed for inert gas ion beam etching as well as for reactive ion beam etching. Back–side cooling, SIMS for end point detection, interface for clean room, beam monitoring with Faraday cup array and other helpful features are available.

(R)–IBE450

TECHNICAL DATA

WORK PIECE DATA

Diameter:	Ø450 mm (Ø18")
Thickness:	50 mm (2")
Weight:	max. 50 kg (110 lbs)
Contact angle:	0 – 90°
Rotation speed:	0 – 10 rpm
Shape:	plane, spherical, aspherical, freeform

SINGLE LOAD LOCK SYSTEM

Loading time:	< 2min.
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AXIS SYSTEM

Type: 450	X, Y, Z, A, B
Travel:	X = 1100 mm
	Y = 500 mm
	Z = 300 mm
	A = 0 – 90°
	B = 360°

DIMENSIONS

Weight:	7000 kg (15400 lbs)
WxHxD:	2.5 m x 3.6 m x 2.0 m (98" x 142" x 79")
Footprint:	4 m x 4 m (157" x 157")

